

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of

Confirmation No. 2189

Allowed: February 21, 2007

NAGATA et al.

Atty. Ref.: 1035-499

Serial No. 10/795,981

Group: 2871

Filed: March 10, 2004

Examiner: T. Duong

For: ACTIVE MATRIX SUBSTRATE, METHOD OF MANUFACTURING THE SAME, AND IMAGE SENSOR INCORPORATING THE SAME

\* \* \* \* \*

May 3, 2007

**Mail Stop: Issue Fee**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE**

The instant application was allowed February 21, 2007. However, the Reasons for Allowance are not commensurate with the scope of the claims.

For example, the reasons for allowance are directed toward claim 9, but are not commensurate with other independent claims 12, 14, 35 and 42. Certain recitations in the reasons for allowance are not present in claims 12, 14, 35 and 42 and these claims are not limited to the content of the reasons for allowance.

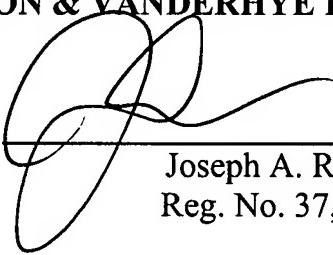
Please let me know if you should have any questions.

Respectfully submitted,

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